SRF LIMITATIONS

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The Real World







Characteristics of Residual Surface Resistance

- No strong temperature dependence
- No clear frequency dependence
- Not uniformly distributed (can be localized)
- Not reproducible
- Can be as low as $1 n\Omega$
- Usually between 5 and 30 $n\Omega$
- Often reduced by UHV heat treatment above 800C





Origin of Residual Surface Resistance

- Dielectric surface contaminants (gases, chemical residues, dust, adsorbates)
- Normal conducting defects, inclusions
- Surface imperfections (cracks, scratches, delaminations)
- Trapped magnetic flux
- Hydride precipitation
- Localized electron states (photon absoption)





A parallel magnetic filed is expelled from a superconductor. What about a perpendicular magnetic field?



The magnetic field will be concentrated in normal cores where it is equal to the critical field.













A fraction H/H_c of the material will be in the normal state.

This will lead to an effective surface resistance $R_n(H/H_c)$

For Nb: $R_{eff} \approx 0.3$ to 1 n Ω /mG around 1 GHz

While a cavity goes through the superconducting transition, the ambient magnetic filed cannot be more than a few mG.

The earth's magnetic shield must be effectively shielded.

In cavities made of composite materials, thermoelectric currents can cause trapped magnetic field.











Q Disease

Cavities that remain at ~100K for an extended period of time experience a sharp increase of surface resistance







Q Disease

At room temperature, the hydrogen moves freely through niobium

At lower temperature, H precipitates to form a hydride with poor superconducting properties: Tc=2.8 K, Hc=60 G

At room temperature the required concentration to form a hydride is 10³-10⁴ ppm

At 150K it is <10ppm

Can be eliminated by baking cavity at 600-800C





High Field Q-Drop

- Decrease of Q at high field not associated with x-rays
- Still an area of investigation
- Many models
 - Magnetic field related
 - Electric field related
- Strong indication that it is related to the concentration of oxygen at the surface
- Reduced or eliminated by mild baking around 120C







High Field Q-Drop

Pollution Model

- Important impurities in Nb are O, N, C, H
- A "pollution layer" (1- 10 nm) of high O concentration resides below the oxide (some spotty evidence for this from surface analysis)
- This layer weakens the superconducting properties of the thin layer, e.g., by lowering Hc1 and Hsh
 - Magnetic flux begins to penetrate at lower field, and cause RF losses.
- At 100 C, 48 hours, O diffuses (typically 100 nm)
 - N and C are unlikely to be responsible because these diffuse much more slowly compared to Nb (<< 1 nm)
- Baking dilutes the pollution layer, raising Hc1 and Hsh.





High Field Q-Drop



E_{acc} [MV/m]









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SNS HB54 Qo versus Eacc Multipacting limited at 16MV/m 5/16/08 cg







Multipacting is characterized by an exponential growth in the number of electrons in a cavity

Multipacting requires 2 conditions:

Electron motion is periodic (resonance condition)

Impact energy is such that secondary emission coefficient is >1













Secondary Emission in Niobium

STUDIES OF MULTIPACTING IN AXISYMMETRIC CAVITIES FOR MEDIUM-VELOCITY BEAMS*

W. Hartung

National Superconducting Cyclotron Lab, Michigan State University, East Lansing, Michigan

F. Krawczyk

Los Alamos National Laboratory, Los Alamos, New Mexico

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Secondary Emission in Niobium

INFLUENCE OF VARIOUS VACUUM SURFACE TREATMENTS ON THE SECONDARY ELECTRON YIELD OF NIOBIUM

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Multipacting was "eliminated" by rounding the shape of the pill-box cavity







Multipacting Simulatiom

TRAJECTORIES # EMAX= -14.260 MV/M BMAX= 224.389 GAUSS







SLANS + SMULTIP, $\omega \Delta t = \pi$

bnds 20 eV to 3 keV; $K_i = 2 \text{ eV}, \alpha_i = 0$







Localized heating

Hot area increases with field

At a certain field there is a thermal runaway, the field collapses

sometimes displays a oscillator behavior

sometimes settles at a lower value

sometimes displays a hysteretic behavior









Thermal breakdown occurs when the heat generated at the hot spot is larger than that can be evacuated to the helium bath

Both the thermal conductivity and the surface resistance of Nb are highly temperature dependent between 2 and 9K











Residual Resistance Ratio

RRR is the ratio of the resistivity at 300K and 4.2K

 $RRR = \frac{\rho(300K)}{\rho(4.2K)}$

RRR is related to the mean free path. For Nb: $l(T = 4.2K) \approx 27 RRR$ (Å)

RRR is related to the thermal conductivity For Nb: $\lambda(T = 4.2K) \approx RRR / 4 (W. m^{-1}. K^{-1})$





Residual Resistance Ratio

Table 6.1: Expected residual resistivity ratio contribution for niobium for 1 ppm wt of impurities^a

Element	RRR	Element	RRR
Н	2640	Zr	$102\ 000-239\ 000$
Ν	4230	$_{ m Hf}$	200 000
\mathbf{C}	4380	W	$262\ 000-721\ 000$
0	5580	Mo	$717\ 000$
Ti	$53\ 700$	Ta	$1\ 140\ 000$

^aThe ideal RRR due to phonon scattering is 35 000. To obtain the RRR one must add the resistance contributions for each impurity element in parallel to the resistance contribution from phonons.





Thermal Conductivity of Nb



Breakdown field given by (very approximately):

$$H_{tb} = \sqrt{\frac{4\kappa_T (T_c - T_b)}{r_d R_d}}$$

T: Thermal conductivity of Nb R_d : Defect surface resistance T_c : Critical temperature of Nb $T_{\rm h}$: Bath temperature

Niobium Purification

 Can produce high Nb purity by e-beam melting in a vacuum furnace

- Currently industry produces
 RRR 300-400 Nb.
- Reactor grade Nb is RRR = 40
- Theoretical limit is RRR = 32,000.

RRR: Residual resistance ratio = resistivity at room temperature divided by the resistivity at 4.2 K (in the normal conducting state!). $_T$ scales linearly with RRR.

Niobium Purification

- After cavity or half-cell is produced
 - Heat in vacuum furnace to ~ 1400 C
 - Evaporate Ti on cavity surface
 - Use titanium as getter to capture impurities
 - Later etch away the titanium
 - Doubles the purity (RRR ~ 600 if originally RRR = 300)

Post Purifying Niobium

The Real World

Characterized by an exponential drop of the Q

Associated with production of x-rays and emission of dark current

SNS HB54 Qo versus Eacc Multipacting limited at 16MV/m 5/16/08 cg

SNS HTB 54 Radiation at top plate versus Eacc 5/16/08 cg

DC Field Emission from Ideal Surface

Fowler-Nordheim model

Field Emission in rf Cavities

$$J = \frac{k}{\Phi} \frac{1.54 \times 10^{-6} (\beta E)^{5/2}}{\Phi} \exp\left(-\frac{6.83 \times 10^9 \Phi^{3/2}}{\beta E}\right)$$

 β : Enhancement factor (10s to 100s)

k : Effective emitting surface

Geometrical Origin of Field Enhancement

Smooth particles show little field emission

Simple protrusions are not sufficient to explain the measured enhancement factors

Possible explanation: tip on tip (compounded enhancement)

Localized Defects

Example of Field Emittors

Fig. 11 Example of a scratch and a particle on a niobium surface.

V

Example of Field Emitters

Stainless steel

Enhancement by Absorbates

Adsorbed atoms on the surface can enhance the tunneling of electrons from the metal and increase field emission

Surface electric field is not a fundamental limitation

Surface fields above 100 MV/m over many cm² have been maintained cw in superconducting cavities (>200 MV/m for ms)

However field emission is still the main limitation

The main cause of field emission is particulate contamination

Contamination Prevention

Sources of contamination

- Processing Chemicals (filtered!)
- High Purity Water (>18 M Ω cm, <0.02 μ m filter)
- Clean Room environment (entrance, class 10)
- Particulates on equipment,tooling,hardware,clothing, gloves..

Contamination control

- Stringent control of processes and procedures
- In-line monitoring of particulate levels in air and liquids
- Scheduled maintenance
- "Blow-off" with filtered N₂, monitored by particle counter
- Use of appropriate hardware (e.g. bolts..)
- Clever designs (e.g.gaskets, clamp rings, fixtures...)
- Consistent use of "best practices" through whole assembly process

Contamination Prevention

Continuous-flow rinse

Ultrapure water (18 M Ω -cm) must be used for all treatments

High pressure rinsing (HPR)

 Rinsing of cavities with up to 1000 psi (100 bar) water jets removes many particles.

High Pressure Rinse Systems

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Clean Rooms

All cavities and vacuum components are assembled in a clean rooms (class 100 or better, <100 particle per ft³ >0.5µm)

Components and tooling must be designed to be clean room compatible

TESLA cavity

Clean Rooms

Post Processing Contamination

Contamination can occur during string and cryomodule assembly

- Accelerator beam lines are not clean
- Particulate can migrate from beam line to cavities
- Vacuum accidents happen
- Field emission can occur or increase during operation

High power processing Helium Processing

High Power Processing

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High Power Processing

Helium Processing

Helium gas is introduced in the cavity at a pressure just below breakdown (~10⁻⁵ torr)

Cavity is operating at the highest field possible (in heavy field emission regime)

Duty cycle is adjusted to remain thermally stable

Field emitted electrons ionized helium gas

Helium ions stream back to emitting site

Cleans surface contamination

Sputters sharp protrusions

Helium Processing

Helium Processing in CEBAF

Maximum SRF Cavity Voltage per Cryomodule in CEBAF

(Eight 0.5 meter, 1497 MHz srf cavities per cryomodule)

Jefferson Lab

Helium Processing in CEBAF

Improvement of Cavity Performance with Helium Processing

Distribution of Maximum Gradients by Type of Limitation

Helium Processing in CEBAF

CEBAF Downtime Distribution

CEBAF Downtime Contribution by System - FY99

Time Evolution of Performance (DESY)

